	,_	<b>)</b> 2
• /	-	•

L Number	Hits		DB	- Time stamp
3	6	(((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or	USPAT;	2003/10/13 21:13
		deoxidiz\$3 or anodiz\$3) and metal)) and	US-PGPUB;	
		(mask\$3 or resist\$3 or photoresist) same	EPO; JPO; IBM TDB	
		(aluminum or "Al" or steel or titanium or	IDM_IDD	
		"Ti")) and (mask\$3 or resist\$3 or		
		photoresist) same (\$4urethane adj3		
·		\$4acrylate or \$4urethane adj3 \$4acrylate))		
		and (mask\$3 or resist\$3 or photoresist)		
		same (peel\$4 or pull\$4 or remov\$4 or		
		lift\$3 adj off)) and (mask\$3 or resist\$3		
		or photoresist) same (scrib\$4 or cut\$4 or		
4	25	mark\$4 or scrap\$4) ((mask\$3 or resist\$3 or photoresist) same	HODAM	0000/10/10
•	2.5	(( deoxidiz\$3 or anodiz\$3) and metal)) and	USPAT;	2003/10/13 21:14
		(peel\$4 or remov\$4 or scrib\$4 or pull\$4 or	US-PGPUB; EPO; JPO;	
		lift\$3 adj off or cut\$4 or scrap\$4) near3	IBM TDB	
		(mask\$3 or resist\$3 or photoresist) same	TDII_TDB	
		(seal\$3)		
5	1		USPAT;	2003/10/13 21:18
		same ((deoxidiz\$3 or anodiz\$3) and metal)	US-PGPUB;	
			EPO; JPO;	
6	0	(maghant an magh) and 1 1	IBM_TDB	
0	U	(maskant or mask) and line adj sealer same ((deoxidiz\$3 or anodiz\$3) and metal)	USPAT;	2003/10/13 21:18
		((deoxidizas of anodizas) and metal)	US-PGPUB;	
			EPO; JPO; IBM TDB	]
7	95	(216/42,44,47,48,101-102.ccls. or	USPAT;	2003/10/13 21:20
		430/320,323-324.ccls. or	US-PGPUB;	2003/10/13 21.20
		205/122,135,153,188,320,324.ccls.) and	EPO; JPO;	
		seal\$3 same mask\$3	IBM_TDB	
8	170	(IRGACURE adj "1700") or (IRACURE adj	USPAT;	2003/10/13 21:22
		"1700")	US-PGPUB;	
			EPO; JPO;	
9	29	((IRGACURE adj "1700") or (IRACURE adj	IBM_TDB USPAT;	2002/10/12 01 04
		"1700")) and (wax or (synergist and	US-PGPUB;	2003/10/13 21:24
		triethanolamine))	EPO; JPO;	
			IBM TDB	
-	51785	(mask\$3 or resist\$3 or photoresist) same	USPAT;	2003/06/03 09:04
		((etch\$3 or chemical\$2 adj mil\$3 or	US-PGPUB;	
l		deoxidiz\$3 or anodiz\$3) and metal)	EPO; JPO;	
_	25136	((mask\$3 or resist\$3 or photoresist) same	IBM_TDB	0000/00/
	20100	((etch\$3 or chemical\$2 adj mil\$3 or	USPAT;	2003/06/03 09:05
		deoxidiz\$3 or anodiz\$3) and metal)) and	US-PGPUB; EPO; JPO;	
		(mask\$3 or resist\$3 or photoresist) same	IBM TDB	
		(aluminum or "Al" or steel or titanium or	12100	
		"Ti")		
-	26	(((mask\$3 or resist\$3 or photoresist) same	USPAT;	2003/05/26 16:28
	l	((etch\$3 or chemical\$2 adj mil\$3 or	US-PGPUB;	
	l	deoxidiz\$3 or anodiz\$3) and metal)) and	EPO; JPO;	
		(mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or	IBM_TDB	
		"Ti")) and (mask\$3 or resist\$3 or		
		photoresist) same (\$4urethane adj3		
		\$4acrylate or \$4urethane adj3 \$4acrylate)		

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	922	same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4acrylate or \$4acrylate)) not ((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:27
_	26	same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate)) and (mask\$3 or resist\$3 or photoresist) same (peel\$4 or pull\$4 or remov\$4 or lift\$3 adj off)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:32
	854	(((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4acrylate or \$4acrylate)) not (((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate)) and (mask\$3 or resist\$3 or photoresist) same (peel\$4 or pull\$4 or remov\$4 or lift\$3 adj off)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:32
	6	(((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate) and (mask\$3 or resist\$3 or photoresist) same (peel\$4 or pull\$4 or remov\$4 or lift\$3 adj off)) and (mask\$3 or resist\$3 or photoresist) same (\$crib\$4 or cut\$4 or mark\$4 or scrap\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/13 21:12
-	1560	<pre>(mask\$3 or resist\$3 or photoresist) same (( deoxidiz\$3 or anodiz\$3) and metal)</pre>	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/06/03 09:55
-	308	((mask\$3 or resist\$3 or photoresist) same ((deoxidiz\$3 or anodiz\$3) and metal)) and (peel\$4 or remov\$4 or scrib\$4) adj3 (mask\$3 or resist\$3 or photoresist)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/06/03 09:10
_	495	(peel\$4 or remov\$4 or scrib\$4 or pull\$4 or	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:11

-	511		USPAT;	2003/06/03 09:12
	İ	((deoxidiz\$3 or anodiz\$3) and metal)) and	US-PGPUB;	
		(peel\$4 or remov\$4 or scrib\$4 or pull\$4 or	EPO; JPO;	
		lift\$3 adj off or cut\$4 or scrap\$4) near3	IBM_TDB	
1_	24	(mask\$3 or resist\$3 or photoresist)		
	24		USPAT;	2003/10/13 21:13
		(( deoxidiz\$3 or anodiz\$3) and metal)) and	US-PGPUB;	
		(peel\$4 or remov\$4 or scrib\$4 or pull\$4 or lift\$3 adj off or cut\$4 or scrap\$4) near3	EPO; JPO;	
		(mask\$3 or resist\$3 or photoresist) same	IBM_TDB	
		(seal\$3)		
_	1		HODAM	0000 (10 (10 )
	_	same ((deoxidiz\$3 or anodiz\$3) and metal)	USPAT;	2003/10/13 21:17
		- Tamb ((deomidizes of anodizes) and metal)	US-PGPUB;	
			EPO; JPO; IBM TDB	
-	0	(maskant or mask) and line adj sealer same	USPAT;	2002/10/12 01 10
		((deoxidiz\$3 or anodiz\$3) and metal)	US-PGPUB;	2003/10/13 21:18
		and the same and t	EPO; JPO;	
			IBM TDB	
-	92		USPAT;	2003/10/13 21:18
		430/320,323-324 or	US-PGPUB;	2003/10/13 21:18
		205/122,135,153,188,320,324).ccls. and	EPO; JPO;	
		seal\$3 same mask\$3	IBM TDB	
-	145	THE TENED TO THE TENED AND THE	USPAT;	2003/10/13 21:21
		"1700")	US-PGPUB;	
			EPO; JPO;	
			IBM TDB	
-	23		USPĀT;	2003/10/13 21:24
		"1700")) and (wax or (synergist and	US-PGPUB;	
		triethanolamine))	EPO; JPO;	
	3	//TDCACUDE . 1' #1200#1	IBM_TDB	
	3	((IRGACURE adj "1700") or (IRACURE adj	USPAT;	2003/10/13 15:54
		"1700")) and (cur\$3 or expos\$3 or light\$3 or UV or ultraviolet or actinic or	US-PGPUB;	
		radiates) game (effect and actinic or	EPO; JPO;	
		radiat\$3) same (\$5watt adj per adj square adj \$5meter or "W/cm.sup.2" or	IBM_TDB	
		"W/m.sup.2")		
-	762	(mask\$3 or resist\$3 or photoresist) same	HCDAM.	0000/10/10 15
]		(peel\$4 or pull\$4 or remov\$4 or lift\$3 adj	USPAT;	2003/10/13 16:13
		off) and \$4acrylate and (cur\$3 or expos\$3	US-PGPUB; EPO; JPO;	
		or light\$3 or UV or ultraviolet or actinic	IBM TDB	
		or radiat\$3) same (\$5watt adj per adj	1017_100	
		square adj \$5meter or \$1"W/cm.sup.2" or		
		\$1"W/m.sup.2")		
-	40	(mask\$3 or resist\$3 or photoresist) same	USPAT;	2003/10/13 16:16
		(peel\$4 or pull\$4 or remov\$4 or lift\$3 adi	US-PGPUB;	2003/10/13 10:10
	[	off) and \$4acrylate.ti.ab. and (cur\$3 or	EPO; JPO;	
	ļ	expos\$3 or light\$3 or UV or ultraviolet or	IBM TDB	
		actinic or radiat\$3) same (\$5watt adi per	_	
		adj square adj \$5meter or \$1"W/cm.sup.2")		

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